

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/776,553
Filing Date February 10, 2004
Inventor Weimin Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 1755
Examiner Carol M. Koslow
Attorney's Docket No. MI22-2497
Title: Compositions of Matter and Barrier Layer Compositions

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -See Attached Form PTO-1449

The attached Form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to FEDERAL REGISTER, Vol. 69, No. 182, pg. 56542 (September 21, 2004), no copies of any cited U.S. patents or U.S. published applications are included herewith. Copies of all other cited art are attached.

No admission is made regarding whether the listed references are prior art.

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180.00 OP

Respectfully submitted,

Dated:

July 6, 2005


By:

Jennifer J. Taylor
Jennifer J. Taylor, Ph.D.
Reg. No. 48,711

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2497	SERIAL NO. 10/776,553		
 <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT Weimin Li et al.			
				FILING DATE February 10, 2004	GROUP 1755		
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EXAMINER				DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							

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	AT	Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography", Solid State Technology (March 1997), pp. 109-114.					
	AU	Grant, J., "Hackh's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 27.					
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